## State Drift Optimization of Memristive Stateful IMP Logic Gates

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## INTRODUCTION

The use of memristive devices for new computational architectures enables the application of the same elements as latches and logics, which can significantly enhance the existing computational resources, open new computational paradigms, and reduce costs. Recently, the realization of material implication (IMP) in a gate, cf. Fig.1(a), including a conventional resistor (R<sub>G</sub>) and two TiO2 switches (M<sub>P</sub> and M<sub>O</sub>) was reported to enable stateful logic operations, where the memristive switches serve simultaneously as logic gates [1]. The switching dynamics in TiO<sub>2</sub> memristive devices is, however, significantly affected by electron tunneling through a varying width tunnel barrier w [2], cf. Fig. 1(b), which strongly influences the electrical properties of logical operations. In particular, the resistance at high voltages important for digital applications is considerably reduced, cf. Fig.2. Thus, the linear memristive model can only be used for low voltage analog circuits, while nonlinear modeling has to be performed for digital design.

The design procedure of the IMP gate involves determining the proper values of the circuit parameters ( $R_G$ ,  $V_{SET}$ , and  $V_{COND}$ ) for optimally describing logic behavior. The only existing design procedure [3], based on a linear memristor model, is inconsistent with experimental data.

## IMP GATE OPTIMIZATION

In this work we propose a new design procedure for reliably describing logic behavior at a desired frequency based on a switching dynamic model of  $TiO_2$  memristors [2], for which the

complex switching dynamics arising from ionic motion and modulation of an effective tunneling resistance with voltage and current is properly taken into account.

The initial logic states of the M<sub>P</sub> and M<sub>Q</sub> (p and q) are the inputs of the IMP gate. The final logic state of M<sub>Q</sub> (q) after performing the IMP (including simultaneous application of two negative pulses, V<sub>SET</sub> and V<sub>COND</sub>) is the output of the gate. The only initial state which involves a switching (ON-switching of M<sub>Q</sub>) is State 1 (q  $\leftarrow$  1). The voltages applied during the IMP logic operation tend to reduce the tunneling thickness w from  $w_{\text{off}}$  to  $w_{\text{on}}$ , thus affecting the memristance which is the error source (Fig.3). This phenomenon is named state drift (SD) [3].

The nonlinear memristor model helps reducing this error. Indeed, if the window  $\Delta V_Q = |V_{Q1} - V_{Q3}|$  is large, the error accumulated on  $M_Q$  is minimal. We chose  $R_G$  at fixed different  $V_{COND}$  ( $V_{SET}$  is constant) to boost  $\Delta V_Q$ . As follows from Fig.4,  $R_G$  corresponds to the maximum and is thus uniquely defined by the memristor's properties,  $V_{COND}$  and  $V_{SET}$ .

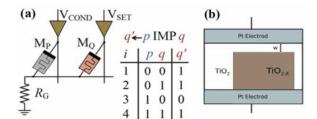
 $\Delta V_Q$  increases with increased  $V_{COND}$  minimizing the SD on memristor  $M_Q.$  However, an increase in  $V_{COND}$  results in an increasing error on memristor  $M_P,$  because it tends to switch, when it should not. There is an optimum  $V_{COND}$  (Fig.5) for which the SD is minimum. Thus,  $V_{COND}$  and  $R_G$  are determined at any  $V_{SET}.$ 

Fig.6 shows only a slight increase of  $V_{SET}$  with the IMP switching time decreased, in contrast to the linear dynamic models. This results in large power consumption benefits at higher IMP speed.

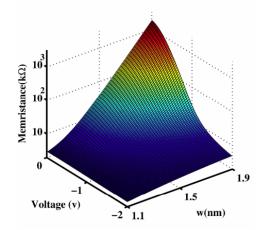
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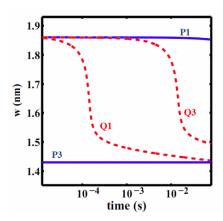
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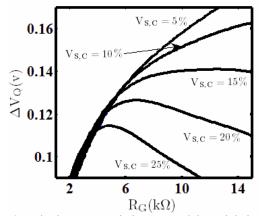
**Fig. 1.** (a) The IMP gate and the IMP truth table [1]. (b) The TiO<sub>2</sub> memristive device cross section [2].



**Fig. 2.** The memristance as a function of V and w. A 0.4nm modulation in w ( $w_{\rm off}$ =1.85nm and  $w_{\rm on}$ =1.45nm [2]) provides a resistance ON-OFF-switching ratio about 40 at 0.2V readout voltage.



**Fig. 3.** The dynamic behavior of w in  $M_P$  and  $M_Q$  during the IMP operation plotted for State 1 and State 3. A high enough voltage modulation on  $M_Q$  ( $\Delta V_Q = |V_{Q1} - V_{Q3}|$ ) and also a high enough  $V_{S,C}$  (= $|V_{SET} - V_{COND}|$ ) are needed to ensure the IMP correct logic behavior in State1 and State 3, respectively.



**Fig. 4.**  $R_G$  is chosen to maximize  $\Delta V_Q$  and thus minimize the error on  $M_Q$  for fixed  $V_{S,C}$  ( $V_{S,C}$  = ( $V_{SET}$ - $V_{COND}$ )/ $V_{SET}$ ).

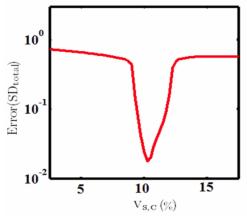
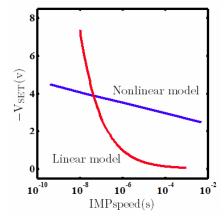


Fig. 5. The total error (state drift) as a function of  $V_{\text{S,C}}$ . The value of  $V_{\text{SET}}$  is chosen based on the minimum error obtained.



**Fig. 6.** (a) Dependence of  $V_{SET}$  on the IMP speed. The absolute value  $V_{SET}$  increases with switching time decreased. However, the decrease is much slower as compared to the one obtained with the linear memristor model.